

CERTIFICATE OF MAILING BY FIRST CLASS MAIL (37 CFR 1.8)

Applicant(s): Yasushi AKIYAMA et al.

Docket No.

2002JP311

Serial No.

10/519,242

Filing Date

December 22, 2004

Examiner

WU, Ives J.

Group Art Unit

1713

Invention **COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME**I hereby certify that this English Language abstract of JP 06-148896 - 2 Pages

(Identify type of correspondence)

is being deposited with the United States Postal Service as first class mail in an envelope addressed to: The

Commissioner of Patents and Trademarks, Washington, D.C. 20231-0001 on September 14, 2005

(Date)

MARIA T. SANCHEZ

(Typed or Printed Name of Person Mailing Correspondence)


(Signature of Person Mailing Correspondence)

Note: Each paper must have its own certificate of mailing.

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 06-148896

(43)Date of publication of application : 27.05.1994

(51)Int.CI. G03F 7/11

G03F 7/004

H01L 21/027

(21)Application number : 04-327610 (71)Applicant : TOKYO OHKA KOGYO CO LTD

(22)Date of filing : 13.11.1992 (72)Inventor : WAKIYA KAZUMASA

KOBAYASHI MASAICHI

TANAKA HATSUYUKI

NAKAYAMA TOSHIMASA

(54) COATING LIQUID FOR RESIST AND RESIST MATERIAL USING THAT

(57)Abstract:

PURPOSE: To prevent the reduction of dimensional accuracy of pattern caused by interference between irradiating light and reflected light from the substrate in a photoresist film by incorporating a water-soluble film forming component and a fluorine-base surfactant.

CONSTITUTION: This resist coating liquid contains a water-soluble film forming component and a fluorine-base surfactant, and the resist material has a interference preventing film consisting of this coating liquid. In this case, the water-soluble film forming component is not limited as far as the component has solubility with water and has transmitting property for irradiating light. For example, this component has such properties that a uniform coating film can be formed by an usual coating means such as spin coating, no modified layer is formed between a film of this coating liquid and a photoresist film when the coating liquid is applied on the photoresist film, and further, a film having small absorption coefft. and high transmittance which sufficiently transmits active rays can be formed. The fluorine-base surfactant is not limited, and preferably an anion type nonmetal ion surfactant is used.

LEGAL STATUS [Date of request for examination] 09.04.1999

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number] 3192505

[Date of registration] 25.05.2001

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office